



PATENT
Customer No. 22,852
Attorney Docket No. 04329.2348

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
)
Iwao HIGASHIKAWA) Group Art Unit: 2851
)
Application No.: 09/615,605) Examiner: Michelle P. Nguyen
)
Filed: July 13, 2000)
)
For: PATTERN FORMING METHOD)
AND LIGHT EXPOSURE)
APPARATUS)
Commissioner of Patents and Trademarks
Alexandria, VA 22313-1450

Sir:

AMENDMENT

In reply to the Office Action dated March 13, 2003, the period for reply extending to June 13, 2003, please amend the application as follows:

IN THE CLAIMS:

Please amend claims 9, 11, and 12, and add new claim 21, as follows:

9. (Amended) A pattern forming method, in which a main surface of a mask blank used to fabricate a photomask is exposed in a desired pattern to form a mask pattern on said mask blank, comprising the steps of:

forming position measuring marks on at least two points on a main surface of said mask blank;

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